



ADIS'12, München May 2012

Structural, elastic, vibrational and electronic  
properties of amorphous  $\text{Al}_2\text{O}_3$  from *ab initio*  
calculations

Gonzalo Gutiérrez and Sergio Davis

Department of Physics, Faculty of Sciences  
Universidad de Chile, Chile.

[www.gnm.cl](http://www.gnm.cl)

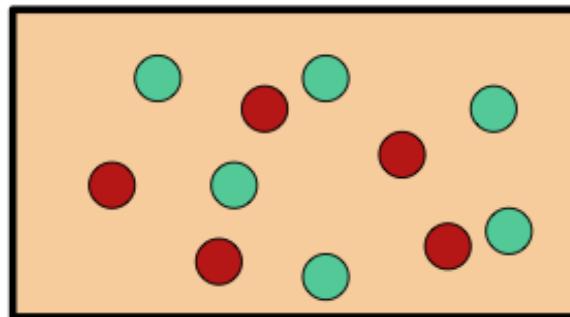
# Molecular Dynamics simulations

Initial conditions:

$$\{\mathbf{r}_i(t_0), \mathbf{v}_i(t_0)\}_N$$



Choice of interatomic potential  $\Rightarrow$  forces



$$N \sim 2000$$
$$V$$
$$E_K = \frac{3}{2} N k_B T$$

- empirical pot
- ab-initio  $\epsilon(R)$

$$V(r) = \frac{q_i q_j}{r} - \frac{C_i C_j}{r^6} + B \exp(ar)$$

Numerical solution to the eqs. of motion

Verlet

$\Delta t: 10^{-15}$  s : time step

Physical properties: temporal average over configurations:  
 $\langle \dots \dots \rangle_t$

- Termodynamics prop.
- structural properties
- dynamical prop.

# Basic diagnostics

- Pair distribution function
- Angular distribution
- Coordination numbers
- Vibrational density of states  
 $D(w)$
- Direct visualization

$$Z_{\alpha(\beta)}(t) = \left\langle \sum_{i=1}^N m_{i\alpha} \vec{v}_{i\alpha}(0) \cdot \vec{v}_{i\alpha}(t) \right\rangle \quad \text{VACF}$$

$$\mathcal{D}_{\alpha(\beta)}(\omega) = \frac{1}{\sqrt{2\pi}} \int \frac{Z_{\alpha(\beta)}(t)}{Z_{\alpha(\beta)}(0)} \exp(-i\omega t) dt$$



**Ceramic material with several technological applications**

due to

high melting point (2327 K),  
extreme hardness (Moh 9) y  
low electrical conductivity

**Structural phase transitions**

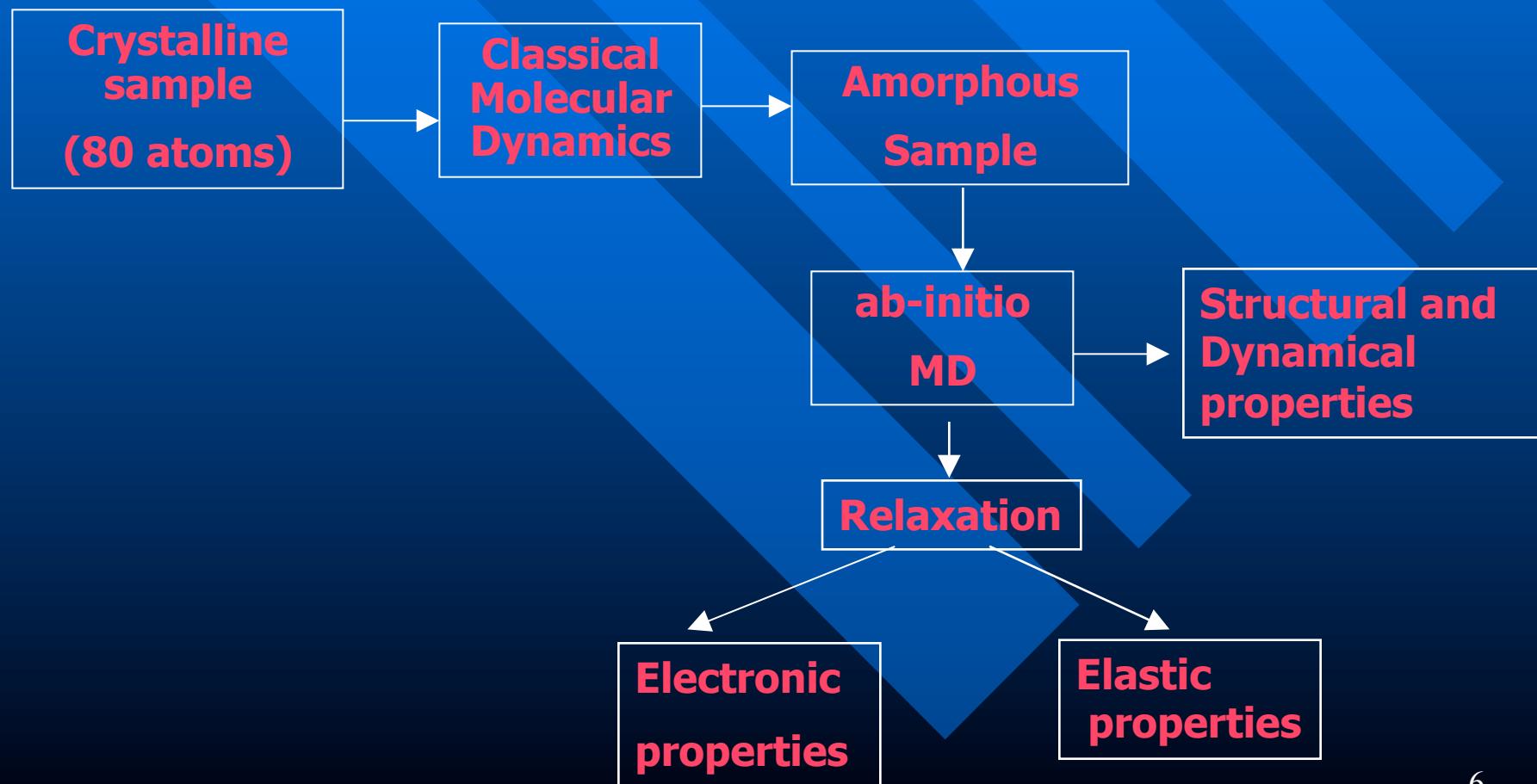
liquid  $\rightarrow \gamma \rightarrow \delta, \theta \rightarrow \alpha$ -alumina  
amorphous (a.o)  $\rightarrow \gamma \rightarrow \theta \rightarrow \alpha$ -alumina

# Amorphous Al<sub>2</sub>O<sub>3</sub>

- Al<sub>2</sub>O<sub>3</sub>-SiO<sub>2</sub> glass is one of the the most important systems in ceramics science
- Many technological applications: catalysis, dielectric, optical devices, microelectronics and thin films devices
- It is present in the surface of aluminum in contact to air (oxidation and passivation phenomena)
- Most alumina thin films are amorphous: they are composed by porous amorphous alumina, but its atomic properties are not well understood so far

# Procedure

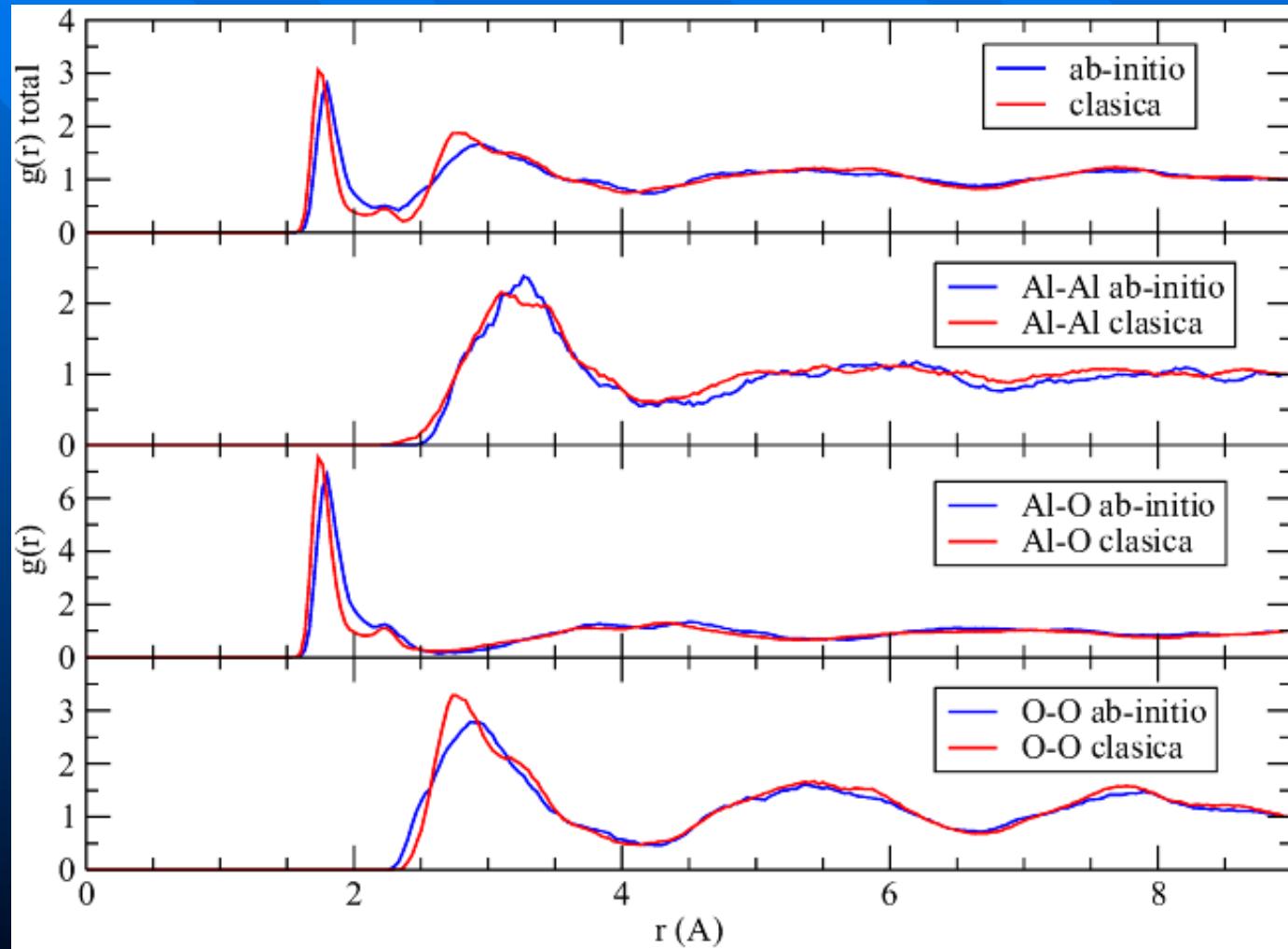
- Combined use of classical an *ab initio* Molecular Dynamics:



# Computational details

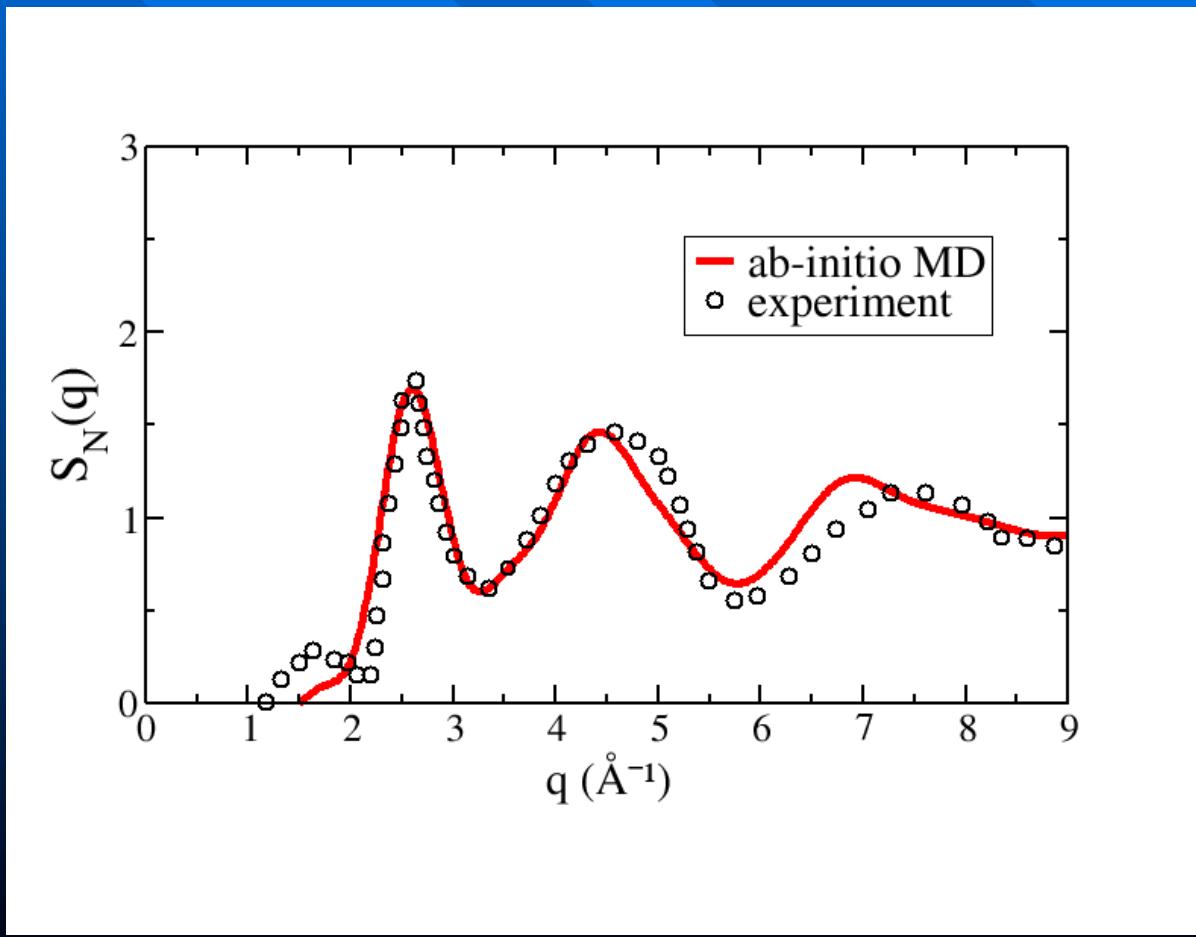
- *ab initio* MD by using VASP (Vienna Ab Initio Simulation Package)
- Density Functional Theory with LDA (local density approximation)
- Ultrasoft pseudopotentials
- Energy cutoff  $E_{cut} = 296,77 \text{ eV}$  (21,81 Ry)
- Only gamma point,  $\Gamma = (0,0,0)$
- Time step of 3 fs for atomic motion

# Pair distribution function



Classical MD: G. G, B. Johansson, PRB 65,104202, (2002); GG et al J. Mat. Sci. 45, 5124 (2010) 8

# Neutron static structure factor: experiments and simulation



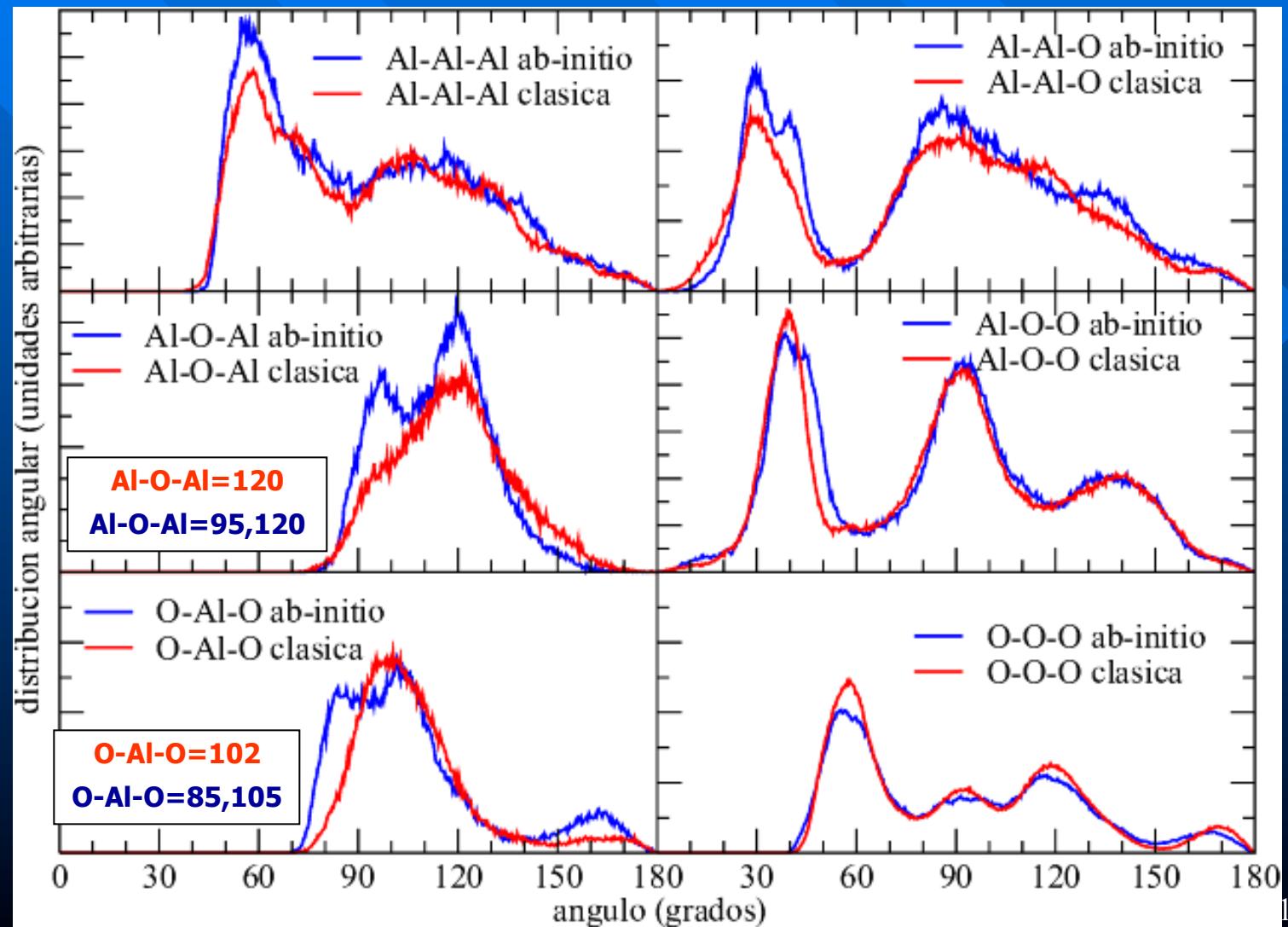
Exp.:  
P. Lamprater,  
R. Kniep,  
Physics B **234**, 405 (1997)

# Interatomic distances and coordination numbers

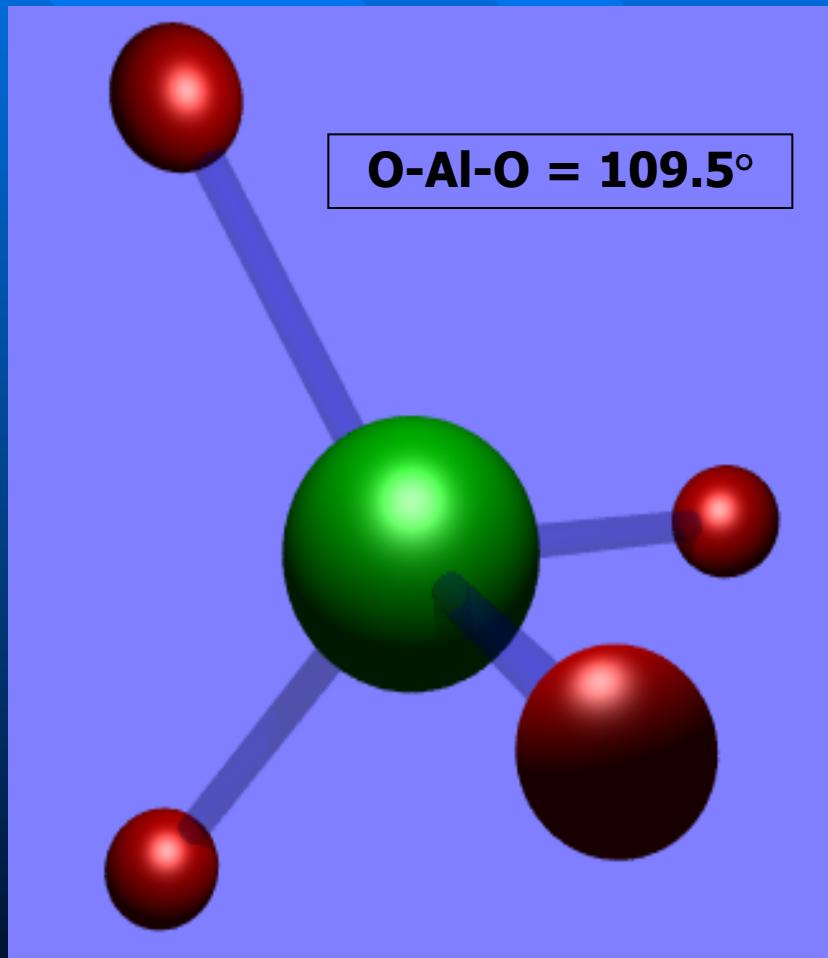
Results	$R_{Al-Al}$ (Å)	$R_{Al-O}$ (Å)	$R_{O-O}$ (Å)
Lamparameter y Kniep	$3,2 \pm 0,55$	$1,8 \pm 0,21$	$2,8 \pm 0,58$
Cassical MD	3,24	1,74	2,77
<i>ab initio</i> MD	3,27	1,80	2,91

Results	$n_{Al-Al}$	$n_{Al-O}$	$n_{O-Al}$	$n_{O-O}$
Classical MD	9,1	3,97	2,65	16,85
<i>ab initio</i> MD	8,9	4,49	2,99	16,46

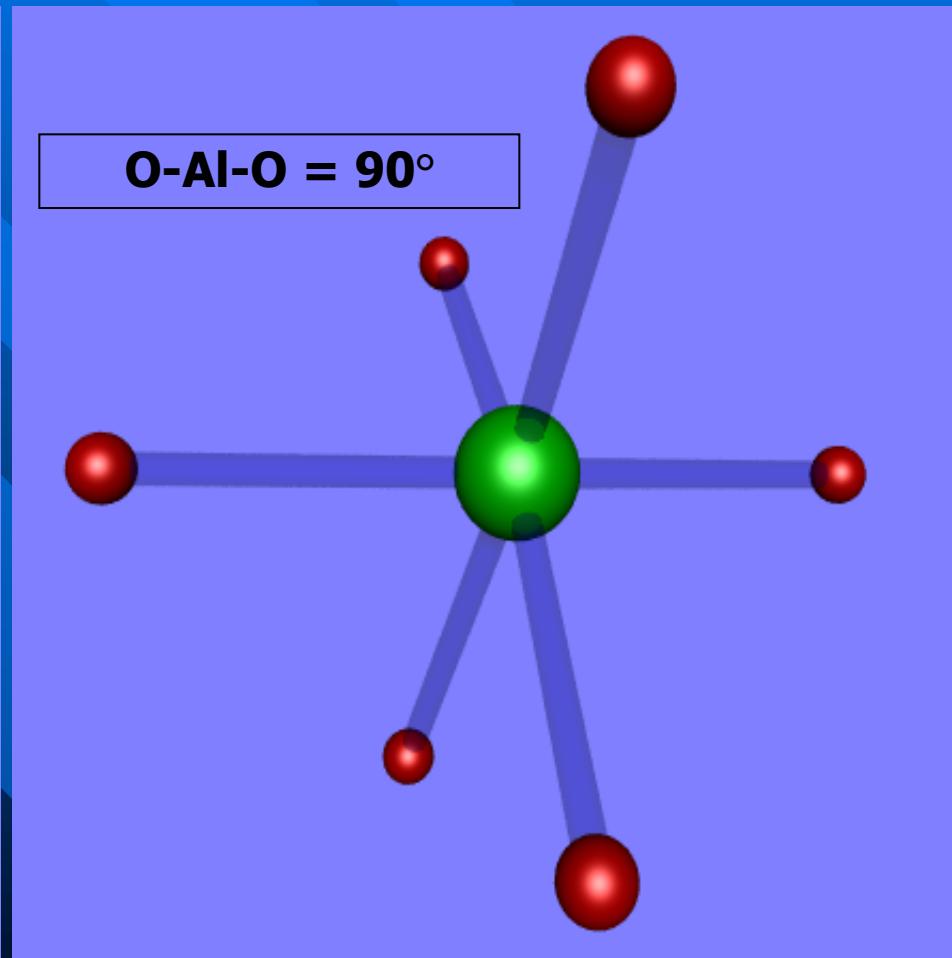
# Angular distribution



# Basic building blocks



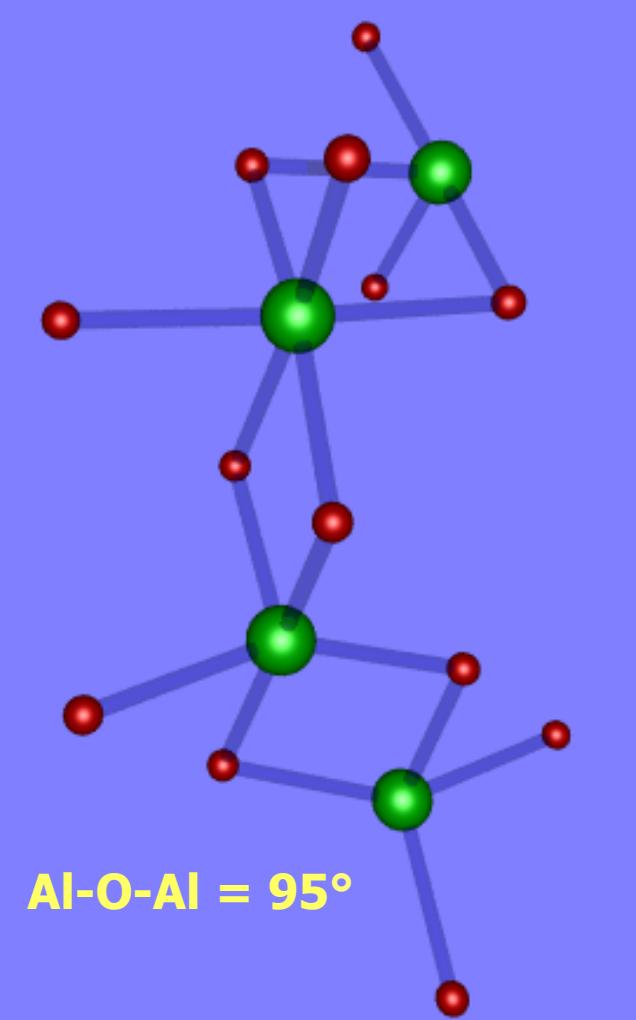
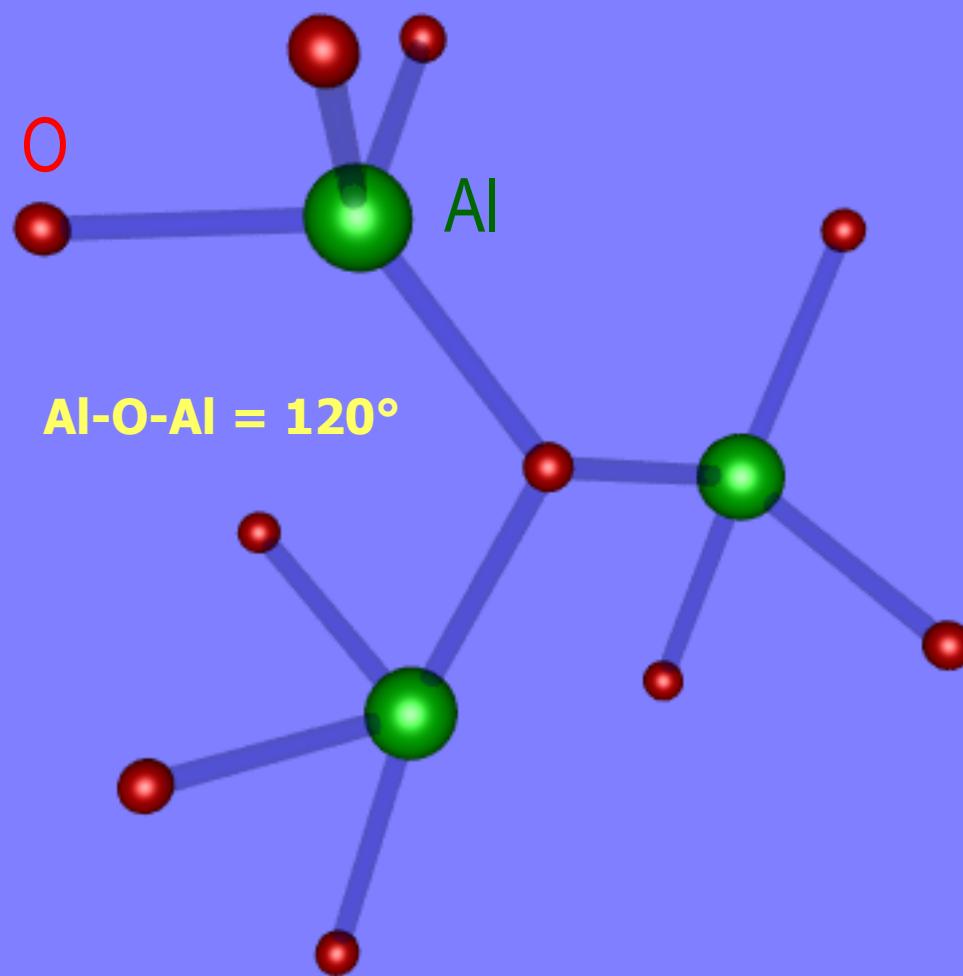
$\sim 52\%$  of AlO<sub>4</sub> terahedron



$\sim 40\%$  of AlO<sub>6</sub> octahedron

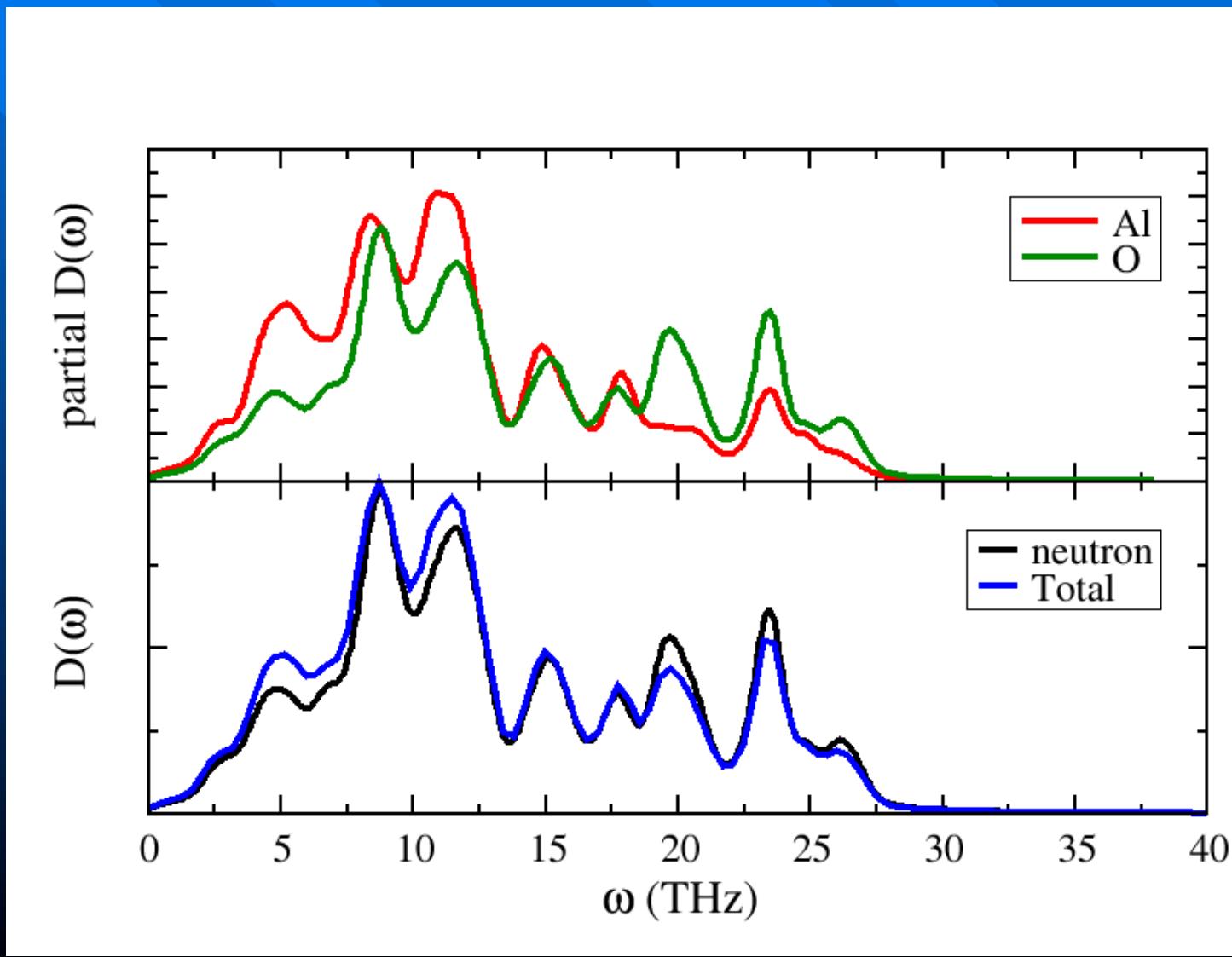
12

# Connectivity of basic units

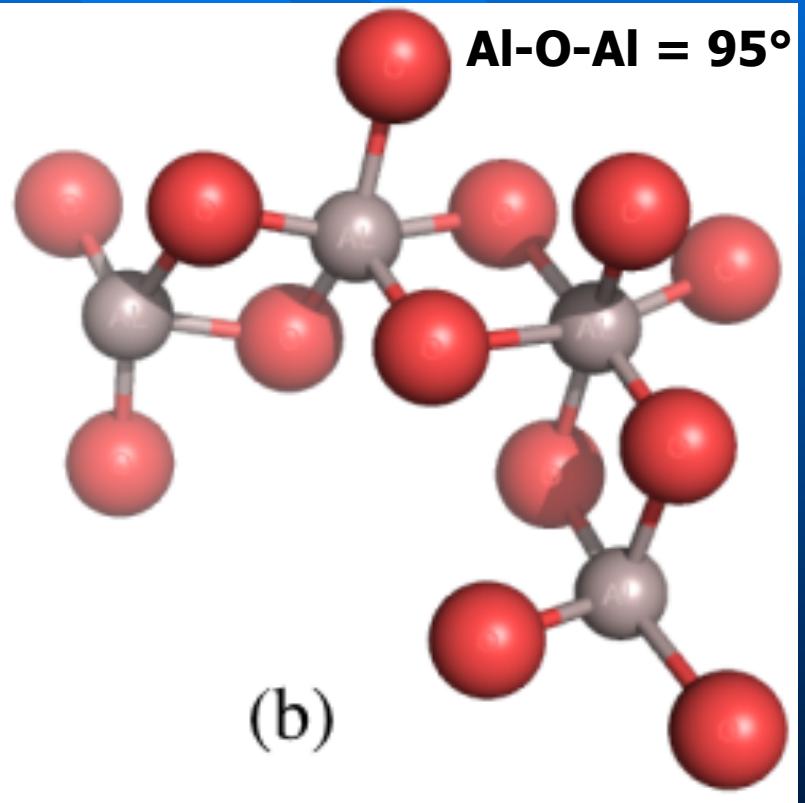
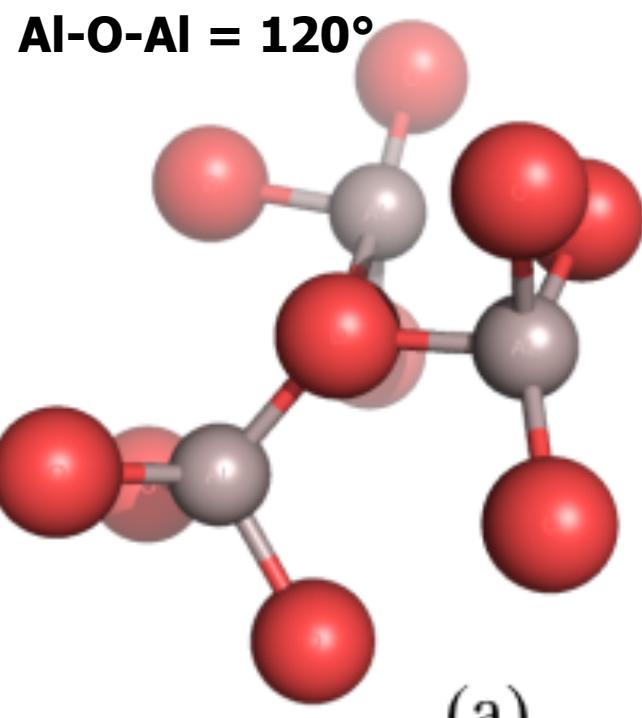


13

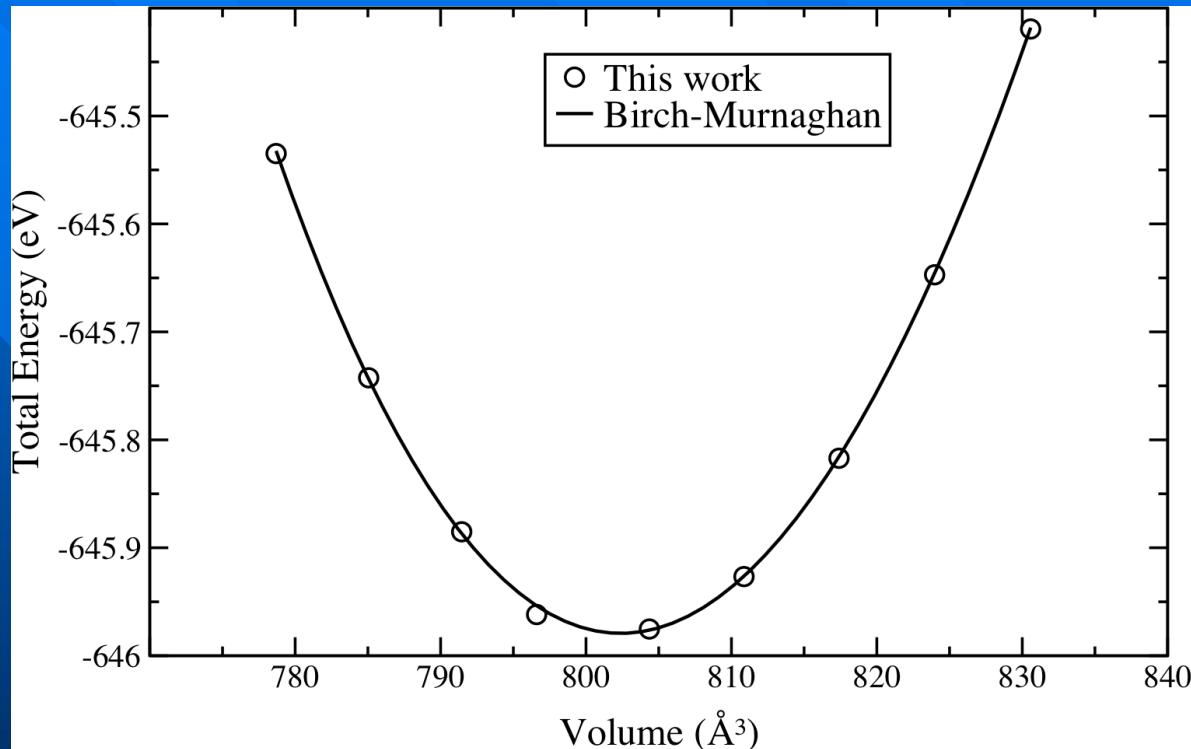
# Vibrational density of states



# Connectivity between basic units

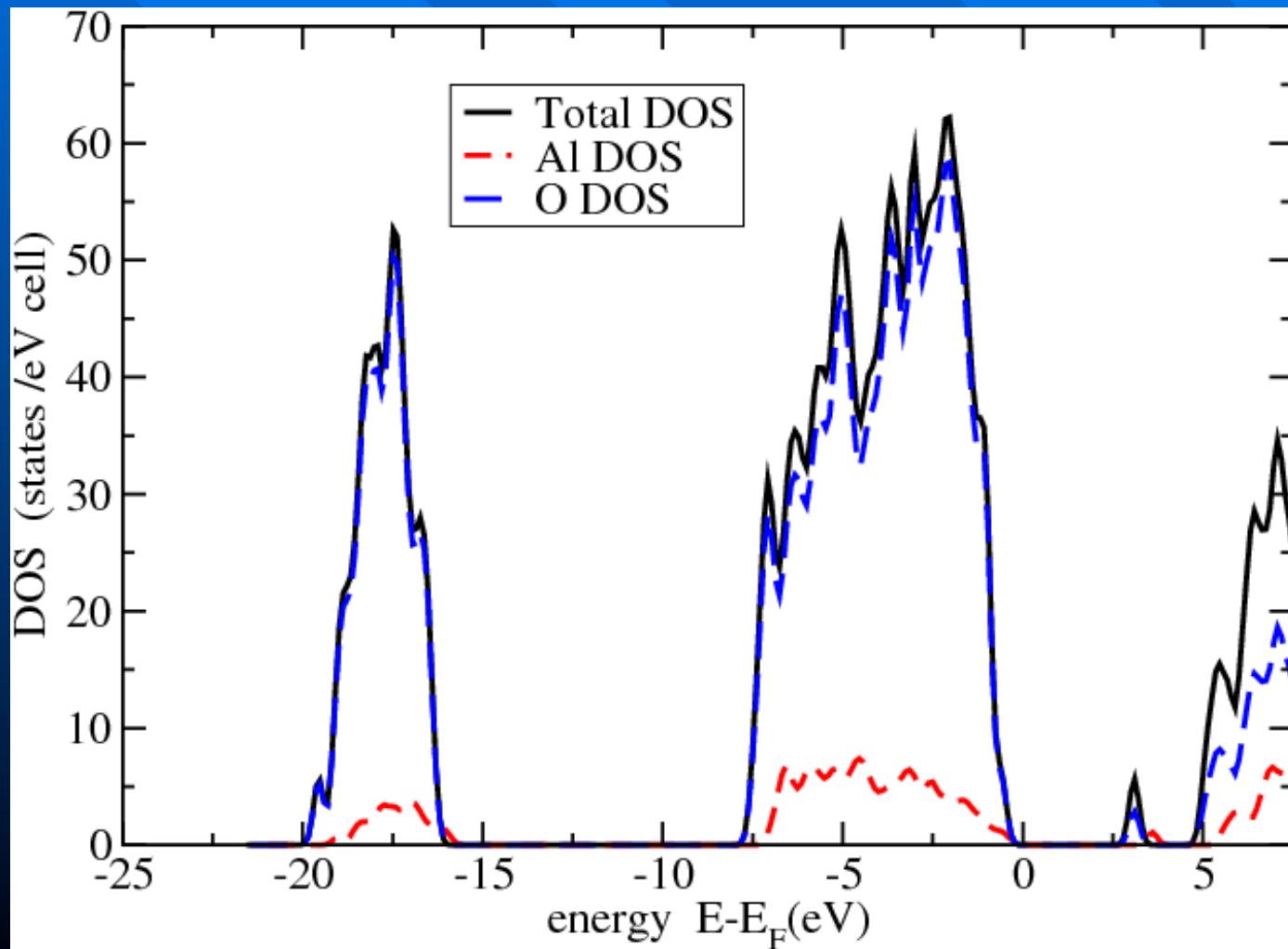


# Elastic properties



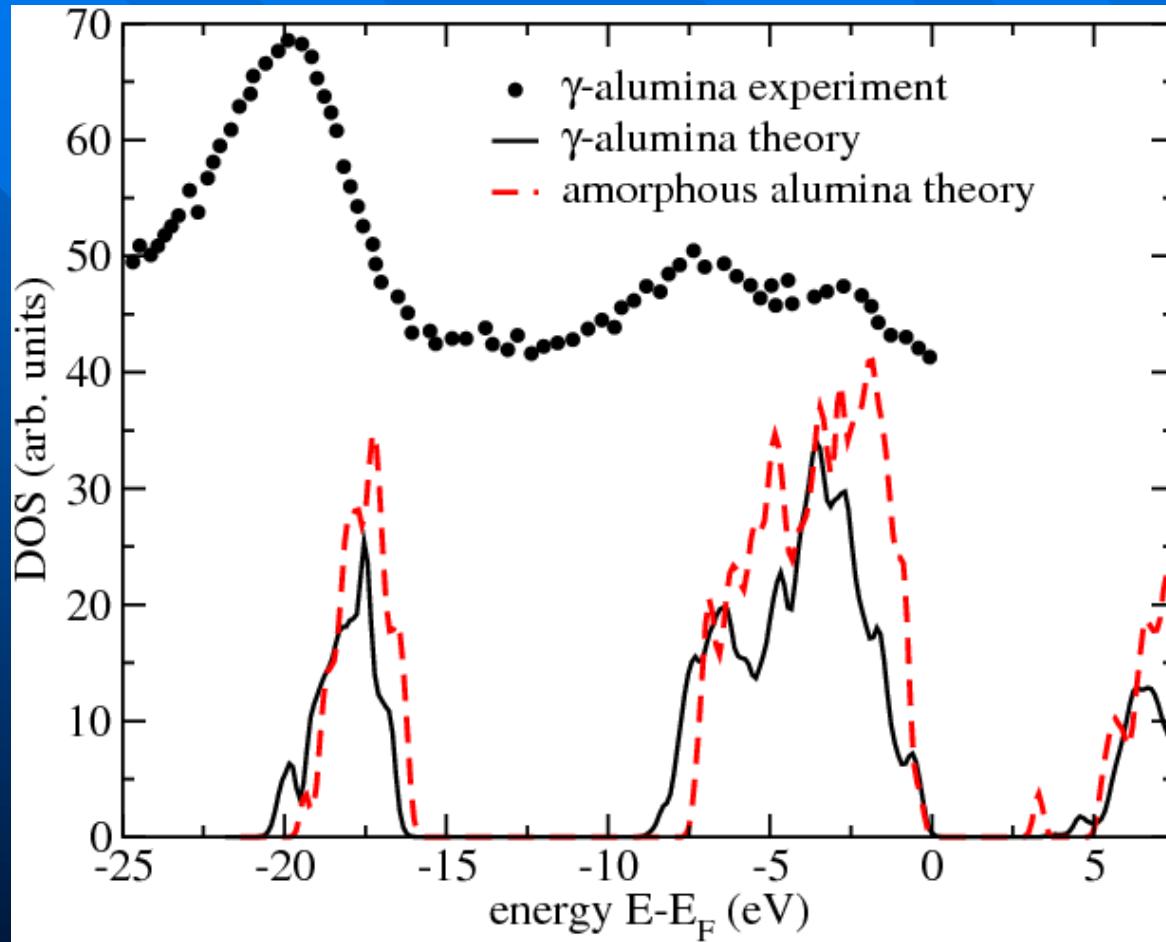
phase	B (GPa)	G (GPa)	E (GPa)	$\nu$
amorph	193.4	141.0	340.3	0.2
Alpha (Wefers & Misra)	253	164	404	0.23

# Electronic density of states



Energy gap  
Exp 3.2 eV  
Theo. 2.6 eV

# Electronic density of states: comparison to $\gamma$ -alumina



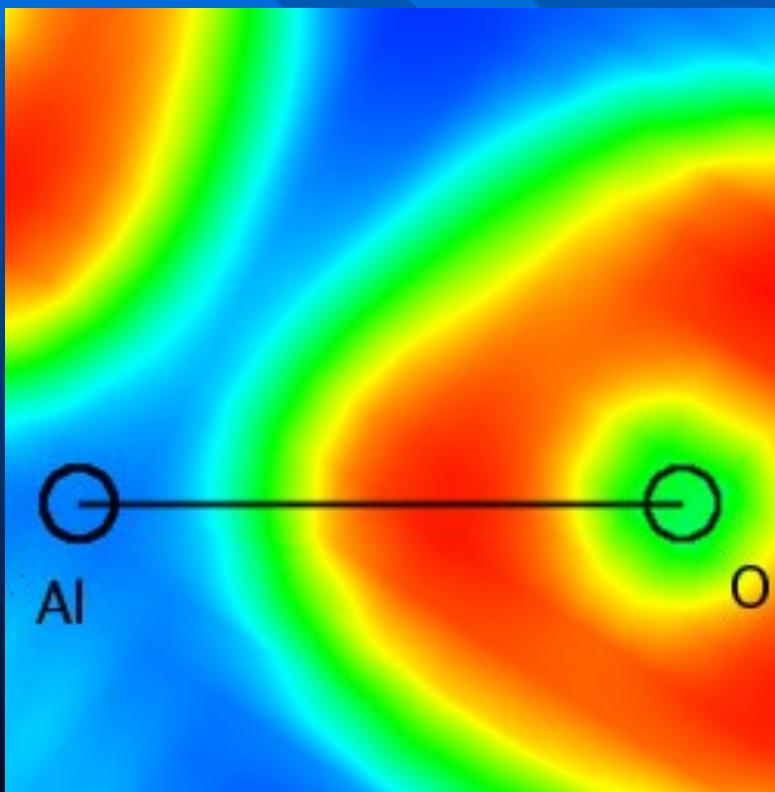
$\gamma\text{-Al}_2\text{O}_3$  Exp: B. Ealet et al. Thin Solid Films **250**, 92 (1994)

Theory: GG, A. Taga. B. Johansson, Phys. Rev. B **65** 012101 (2002)

GG, E. Menéndez, Phys. Rev. B **72** 035116 (2005)

18

# Electron localization function



Charge transfer  
calculated via  
Voronoi analysis:  
 $\text{Al} \sim 2.89$   
 $\text{O} \sim -1.92$

# Different alumina phases

Phase	Density g/cm <sup>3</sup>	Al Coordination Number	Bond length Al-O (Å)
amorphous <sup>b</sup>	3.17	4(76%), 5 (22%)	1.76
	3.9	4(23%), 5(51%), 6(21%)	1.77
	4.2	4(15%), 5(21%), 6(64%)	1.79
a, ab-initio <sup>d</sup>	3.17	4(50%), 5(42%), 6(5%)	1.81
liquid <sup>a</sup>	3.17	3(13%), 4(66%), 5(20%)	1.76
gamma <sup>c</sup>	3.66	4(37%), 6(63%)	1.94 +/- 0.3
theta	3.65	4(50%), 6(50%)	1.9 +/- 0.3
alpha	3.98	6 (100%)	1.97

a) PRE **61**, 2723 (2000),

b) PRB **65**, 104202 (2002), unpublished (2008)

c) PRB **65**, 012101 (2002), PRB, **72**, 035116 (2005)

d) J. Phys.: Condens. Matter **23**, 495401 (2011)

# Conclusions

- Using of ab-initio MD appear new features, absent in (simple) empirical interatomic potential
- The building blocks of the system are  $\text{AlO}_4$  and  $\text{AlO}_6$
- The connectivity of this units is both by the corners (majority) and by the edges (minority)
- The v-DOS present two bands. The low frequency band is related to the inter-unit vibrations, and the high band to the intra-unit vibrations
- $B = 193 \text{ GPa}$ , the lower of all polymorph
- The e-DOS is similar to the one of the crystalline  $\gamma\text{-Al}_2\text{O}_3$ , with a gap of 2.9 eV

# Acknowledgments

- Grant Anillo ACT/24-Chile
- SD thanks Fondecyt 3110017 and GG ENL 10/06  
VRID–Univ. de Chile.